

A METHOD OF IMPROVING THE UNIFORMITY OF ETCHING OF A FILM ON  
AN ARTICLE

ABSTRACT OF THE DISCLOSURE

A method of improving the uniformity of etching of a film on an article, the method including the steps of immersing the article containing the film into a tank of etchant, rotating the article while in the etchant for a desired amount of time so as to cause improved uniformity of etching of the film compared to etching without rotating the article, and removing the article from the tank of etchant. In a preferred embodiment of the invention, the article is a semiconductor wafer.

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